

ABSTRACT OF THE DISCLOSURE

Disclosed is an exposure apparatus which includes an illumination optical system for illuminating an original with exposure light from an exposure light source, a projection optical system for projecting a pattern, formed on the original, onto a photosensitive substrate, a closed or approximately closed casing for accommodating therein at least one of optical components disposed along a light path of the exposure light from the exposure light source to the photosensitive substrate, a purge gas replacing system for supplying a predetermined purge gas into the casing to replace a gas inside the casing with the purge gas, and a controller for changing a supply amount of the purge gas between an exposure period and a non-exposure period.